

(19)

KOREAN INTELLECTUAL PROPERTY OFFICE

## KOREAN PATENT ABSTRACTS

(11)Publication  
number:**20010104140****A**(43)Date of publication of application:  
**24.11.2001**(21)Application  
number:**20000025590**

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(22)Date of filing:

**13.05.2000**

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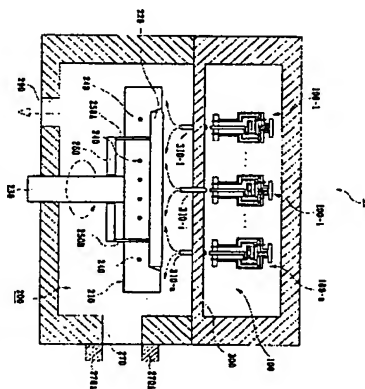
(51)Int. Cl

**H01L 21/18**(54) **MULTI-FUNCTION CHAMBER**

## (57) Abstract:

PURPOSE: A multi-function chamber is provided to diversify processes using the same chamber like a diffusion process, a chemical deposition process and a dry cleaning process by dividing reaction gas activation and surface reaction.

CONSTITUTION: Reaction gas is induced to a reaction gas induction unit. A reaction gas activation heating unit activates the induced reaction gas. A reaction gas pipe makes the reaction gas absorb thermal energy without heat radiation. A total internal reflection coating is performed regarding an internal thermal reflecting part and an external thermal radiation intercepting part to prevent thermal radiation. A reaction gas spraying part uniformly sprays the activated reaction gas.



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## Legal Status

Date of request for an examination (20000513)

Final disposal of an application (registration)

Date of final disposal of an application (20040326)